

Product brief

EVK HELIOS EQ32

Vo2-22-EN



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EVK HELIOS EQ32

320-Pixel Hyperspectral Imaging Camera with an integrated Classification System

- Real-time hyperspectral imaging system
- Operates in the wavelength band from 930 nm to 1700 nm
- Optically distortion corrected, spectrally calibrated, intensity calibrated
- Delivers a classified data stream

Description The EVK HELIOS EQ32 hyperspectral imaging system is a powerful analysis tool, based on non-contact and non-destructive real time infrared imaging spectroscopy. The EVK HELIOS system analyzes chemical properties of objects and makes distinction of material types not visible to color cameras. The internal processing engine delivers qualitative and quantitative information of material streams e.g. analyte concentrations or material compositions. The camera is delivered with a full internal calibration as a plug and play component. HELIOS EQ32 comes in a compact, rugged stainless-steel housing with stress decoupled optomechanics. The system is optimized for real industrial environments and delivers stable calibrated data over the full specified temperature range.

- Key features**
- Operates in Near Infrared (NIR) wavelength range from 0.93 to 1.7 μm
 - Scan rate of 446 Hz at full spectra (248 spectral bands) up to 3.8 kHz using ROI
 - GigE Vision GenICam interface
 - Rugged industrial design. Protection rating IP54
 - Temperature Range 0°C to 50°C with full optical stability
 - Optical system optimized for analytic applications
 - Seamless integration with EVK SQALAR software suite

- Client benefits**
- Internal camera calibration No on-site calibration necessary
 - Embedded data analysis - no need for external PC
 - Real-time imaging system for inline operation
 - Compact and rugged industrial design for use in harsh environments

- Typical applications**
- In-line monitoring and control of production streams
 - In-line measurement of material composition
 - In-line quantitative analysis of analyte concentrations

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